

Serial No. 09/905,172

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: David S. Mui et al.
Serial No.: 09/905,172
Filed: 07/13/2001
Title: ETCH PATTERN DEFINITION USING A CVD ORGANIC LAYER AS AN
ANTI-REFLECTION COATING AND HARDMASK
Art Unit: 1765
Examiner: Deo, Duy Vu Nguyen
Docket No.: 004227USA02/ETCH/SILICON
VIA FACSIMILE 703-872-9310
Mail Stop Fee Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT AND RESPONSE

Sir:

Responsive to the Office Action mailed June 10, 2003 in the above matter, Applicants submit the following amendment and remarks.

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To: Commissioner for Patents

From: David Bonham
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Total pages: 11

Phone:

Date: 9/10/2003

Re: In connection with prosecution in Serial. No.
09/905,172, please find enclosed
(a) an Amendment and Response and
(b) a Terminal Disclaimer to Obviate a Double
Patenting Rejection over a Prior Patent.

CC:

David Bonham

☐ Urgent ☐ For Review ☐ Please Comment ☐ Please Reply ☐ Please Recycle

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